

DJ-LGAD

(Deep-Junction LGAD) A new approach to higher granularity fast timing detectors

> 15° Trento Workshop (2020, Wien) Dr. Simone M. Mazza (SCIPP, UC Santa Cruz), on behalf of the SCIPP UCSC group





LGADs

- LGAD: silicon detector with a thin ($<5\mu$ m) and highly doped ($\sim10^{16}$ P++) multiplication (gain) layer
 - High electric field in the multiplication layer
- LGADs have intrinsic modest internal gain (10-50)
 - $G = \frac{Q_{LGAD}}{Q_{PiN}}$ (collected charge of LGAD vs same size PiN)
 - Better signal to noise ratio, sharp rise edge
- Allows thin detectors (50 μ m, 35 μ m, 20 μ m)
 - Thinner detectors have shorter rise time and less Landau fluctuations
- Time resolution < 30 ps

 $\sigma^2_{timing} = \sigma^2_{time \; walk} + \sigma^2_{Landau \; noise} + \sigma^2_{Jitter} + \sigma^2_{TDC}$

Several vendors of thin LGADs under study
HPK (Japan), FBK (Italy), CNM (Spain), BNL (USA), NDL (China)



LGAD arrays

- Current limitation of LGADs:
 - High fluence radiation hardness \rightarrow but we're getting there!
 - Granularity
- Due to high fields in the multiplication layer the pads needs electrical insulation
 - Protection structure: Junction Termination Extension (JTE)
 - Causes inter pad (IP) gap to 50-150um, also changes with applied bias voltage
 - Limits LGAD granularity to mm scale
- However 50um pitch (and lower) is required for next generation colliders and 4D tracking
 - At least same level as the ATLAS new inner tracker (ITk) needed



Higher granularity LGADs



Several promising approaches to overcome this limit:

- Reverse position of gain layer \rightarrow iLGAD
- AC coupling with output → AC-LGAD (UCSC US patent N. 9,613,993 B2, granted Apr. 4, 2017)
- Trench insulation of pads \rightarrow TI-LGAD
- Some will be discussed in this workshop!

A new approach: deep junction

- Granularity limit is caused by high field near the electrodes
 - What if the field is kept low while maintaining gain?
- Basic inspiration is that of the capacitive field:
 - Large between plates, but surrounded by low-field region beyond the plates
- Use symmetric P-N junction to act as an effective capacitor
- Localized high field in junction region creates impact ionization
- Bury the P-N junction so that fields are low at the surface, allowing conventional granularity
- → "Deep Junction" LGAD (DJ-LGAD)



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Element	Doping Level	Extent in Depth
N isolation layer	Constant doping of density 3e10 N/cm^3	From 0 μm (surface) to 4 μm
N ⁺⁺ gain plate (upper half of gain layer)	Gaussian doping, peak of 3e16 N/cm^3	Peak at 3 μm, falling to 5e12 at 4 μm (sigma = 0.17 μm, FWHM=0.4 μm)
P⁺⁺ gain plate (lower half of gain layer)	Gaussian doping, peak of 3e16 N/cm^3	Peak @ 4.5 μm, falling to 5e12 at 5.5 μm (sigma = 0.17 μm, FWHM=0.4 μm)
P drift region	Constant doping of density 3e12 N/cm^3	4 μm to 50 μm

P++ gain layer is paired with a N++ layer that lowers the field

- Junction is buried ~5 um inside the detector
- Tuning of N+ and P+ parameters important
 - Low field outside of the electrodes while maintaining sufficient gain
 - No need for a JTE
- Termination of gain layer at the edge under study
- DJ-LGAD Baseline design studied with TCAD Sentaurus
- Patent Application SC 2019-978 (UCSC)
 - C. Gee, S. M. Mazza, B. Schumm, Y. Zhao

Electric field configuration

- High field in the buried N++ and P++ junction generates gain
 - Only charge deposited in the P bulk is multiplied
 - (can't be too deep)
- In the P and N bulk electric field is lower
 - But drift speed is saturated
- Simulation example
 - 50um thick device
 - 30um pixel pitch
 - Pads are DC coupled



Electric field configuration

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 - But drift speed is saturated
- Simulation example
 - 50um thick device
 - 20um pixel pitch
 - Pads are DC coupled
 - Small cross talk between pads
 - Gain uniformity of $\pm 4\%$





- Pulse shape temporal profile
- Fast rise time (100ps)
- Full charge collection within 1 ns

- Breakdown voltage over 300V
- Stable simulated gain up to 15
- Studies are ongoing to increase the gain reach



Fabrication of the device







- Fabrication will probably involve epitaxial layer growth
 - For the deposition of the deep junction
 - Needed precision for the deposition to be studied (probably % level)
- First prototype will be produced with in collaboration with **Cactus Material** (AZ)
 - Founded by DoE SBIR "A New Approach to Achieving High Granularity in Low Gain Avalanche Detectors" (34b)
 - Phase-I approved: fabrication of single pad planar device
- Also collaborating with **Brookhaven National Laboratory** for a first production of DJ-LGADs
 - Segmented device but farther in the future
- Also discussing with IHEP Beijing for simulation cross-checks

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Conclusions

- DJ-LGAD: a device with deep junction
 - Avoid high field near the electrodes while maintaining modest gain
 - High field region with multiplication \sim 5um deep
 - Velocity is saturated in the low field regions (P and N)
- TCAD simulation show very promising results
 - Stable gain up to 15
 - 8% gain variation over 30um pitch pads
- First fabrication will be done at BNL and Cactus material (funded by DoE SBIR)







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